

ABSTRACT

RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN

A resist composition is provided that generates an acid upon exposure and has solubility in a developing solution, which is changed by action of an acid, the resist composition including a base material component (A) having solubility in a developing solution, which is changed by action of an acid, and a polyether compound having a weight-average molecular weight of 400 or more, in which a content of the polyether compound is 0.8 to 32 parts by mass with respect to 100 parts by mass of the base material component (A) and a concentration of solid content of the resist composition is 25% by mass or more.

Figure for publication: None